

0996689-09201

FIG. 1A

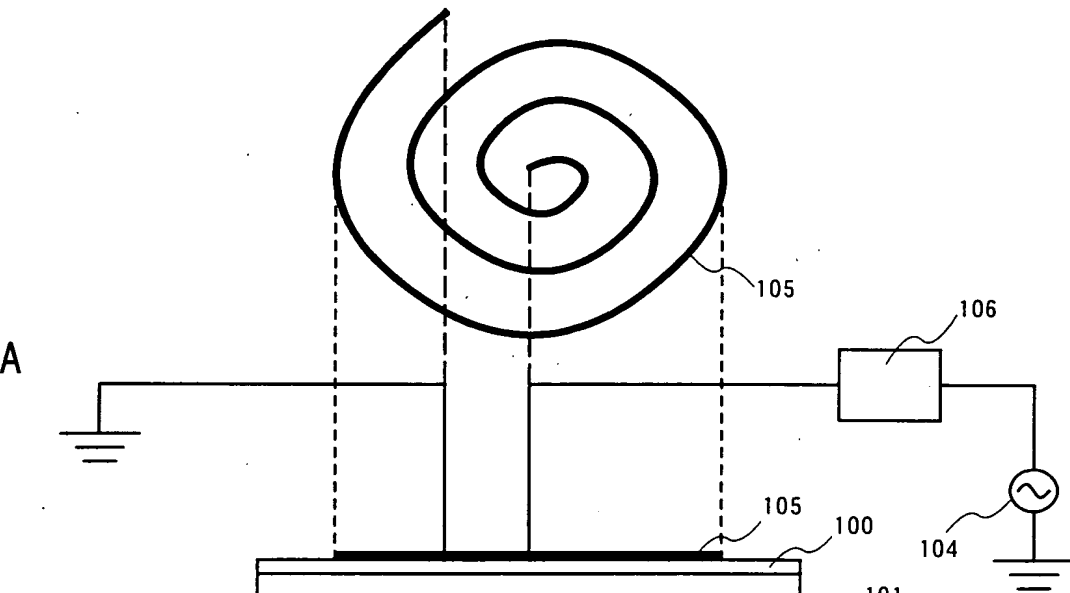


FIG. 1B

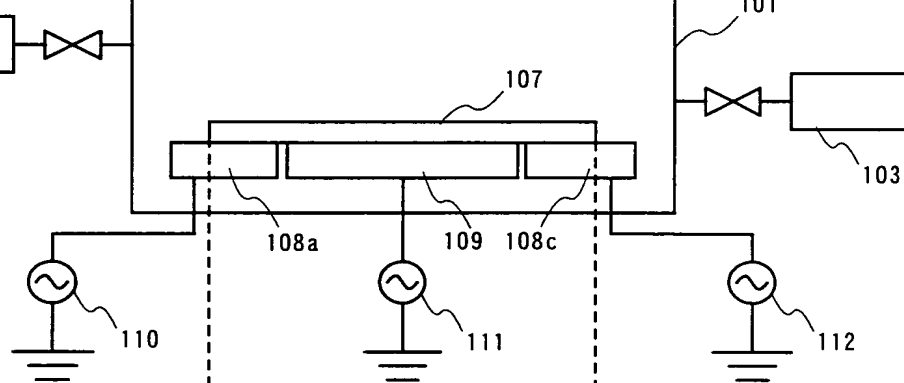


FIG. 1C

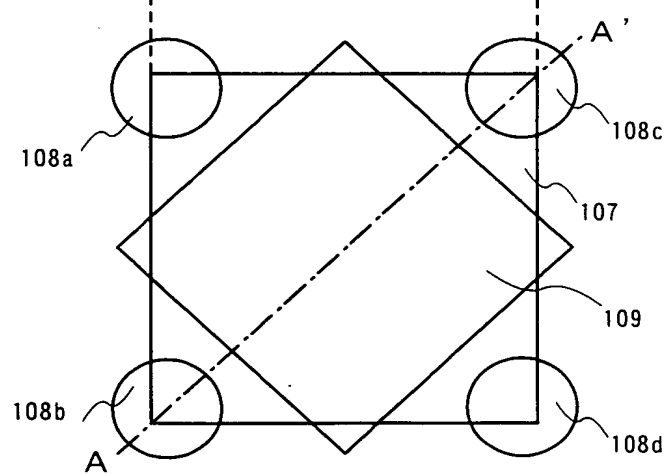


FIG. 2A

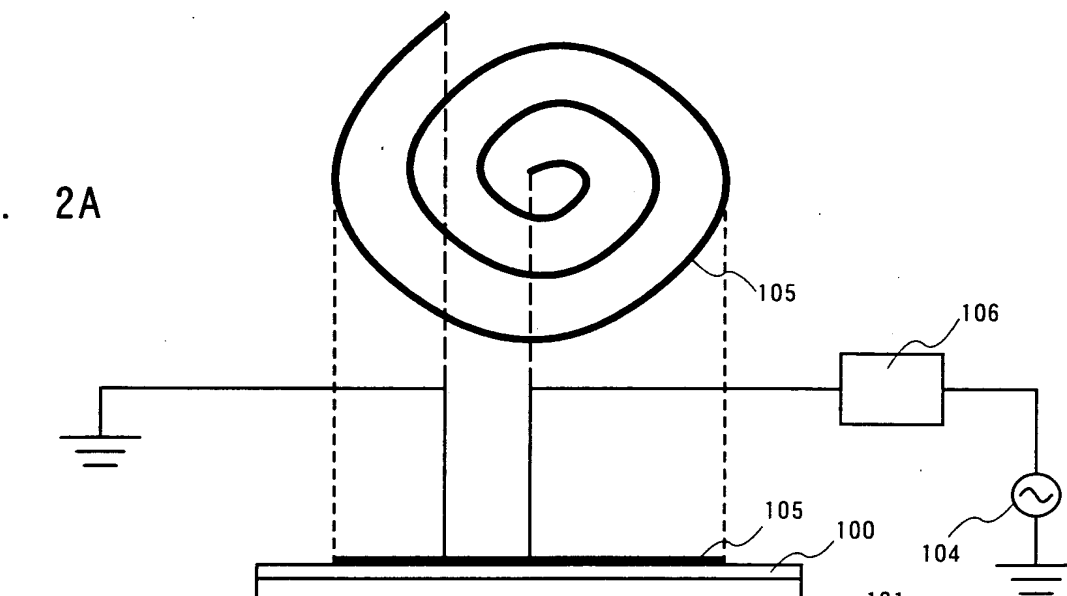


FIG. 2B

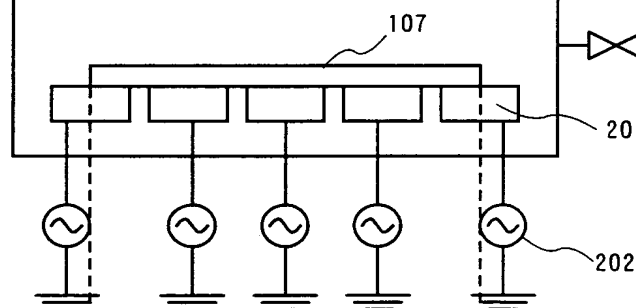


FIG. 2C

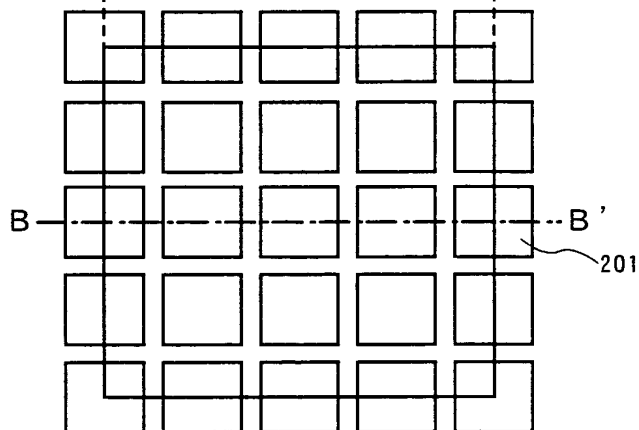


FIG. 3A

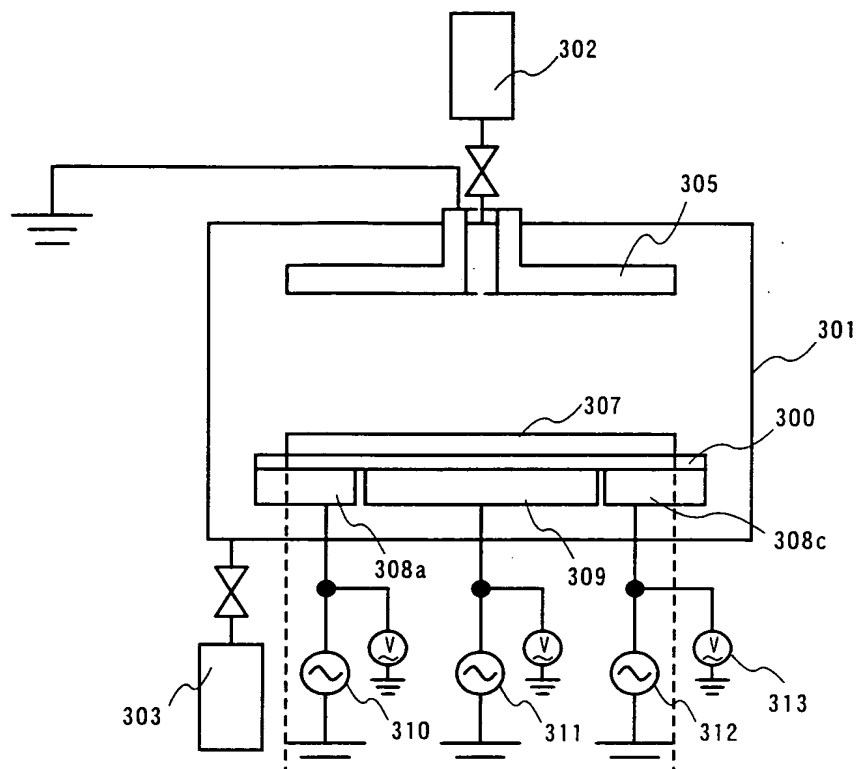
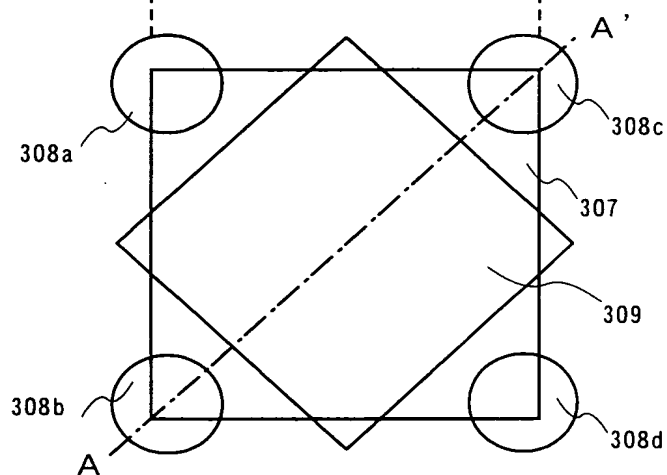


FIG. 3B



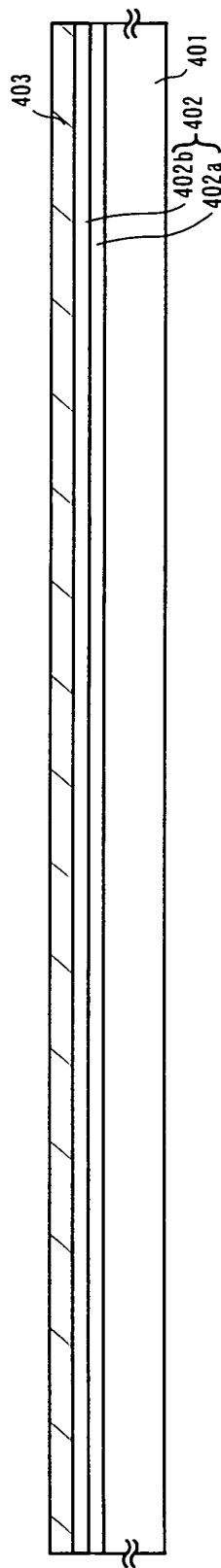


FIG. 4A



FIG. 4B

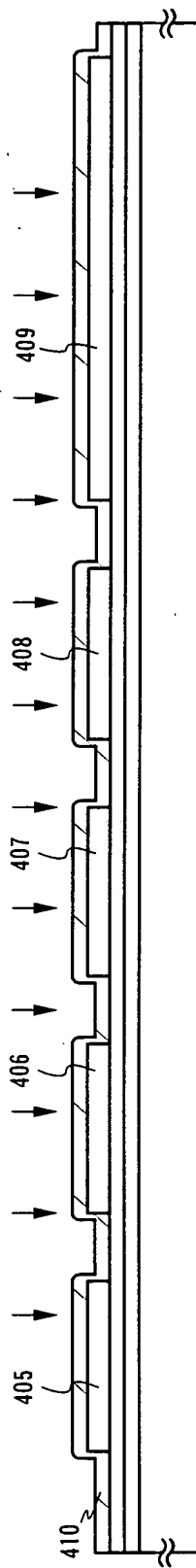


FIG. 4C

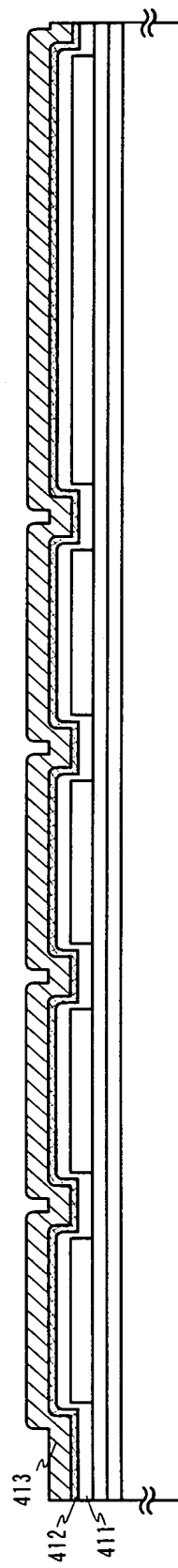


FIG. 4D

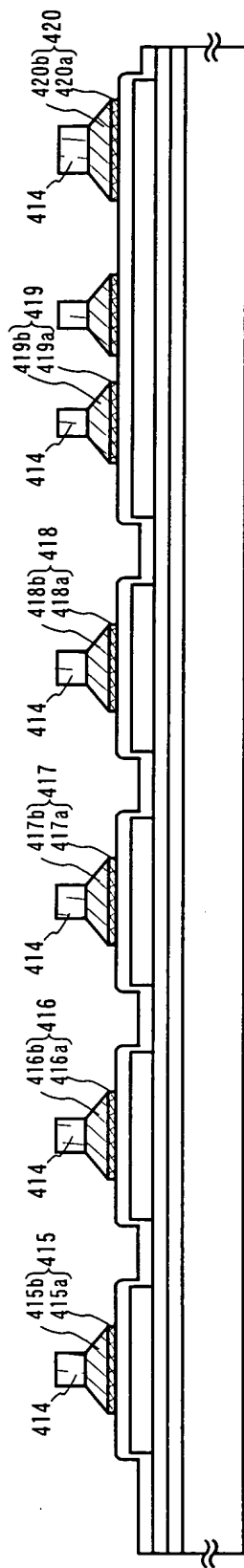


FIG. 5A

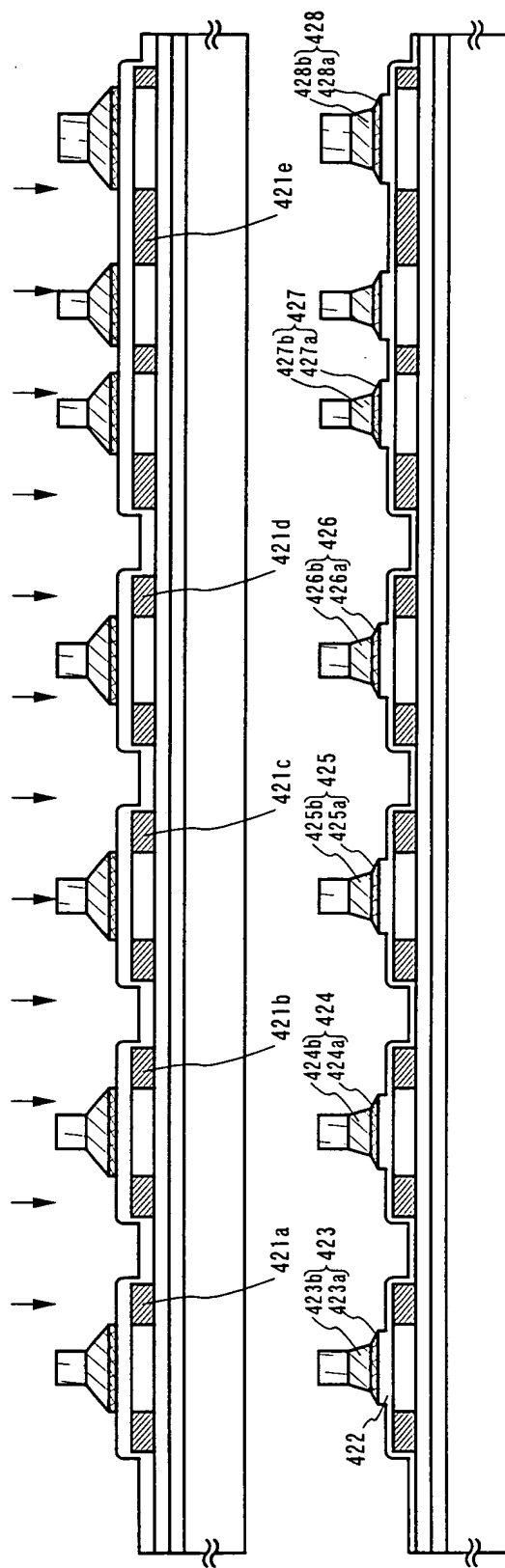


FIG. 5B

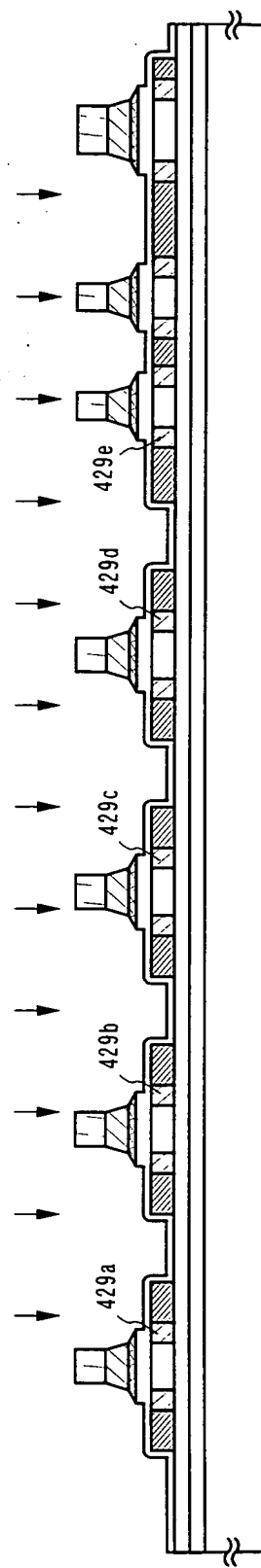


FIG. 5C

FIG. 5D

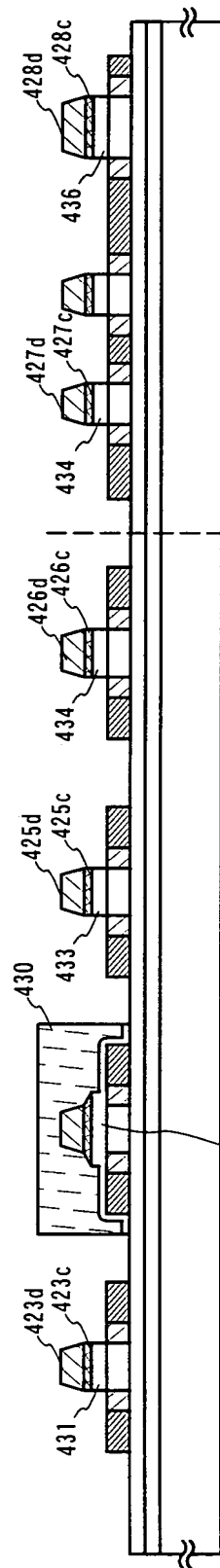


FIG. 6A

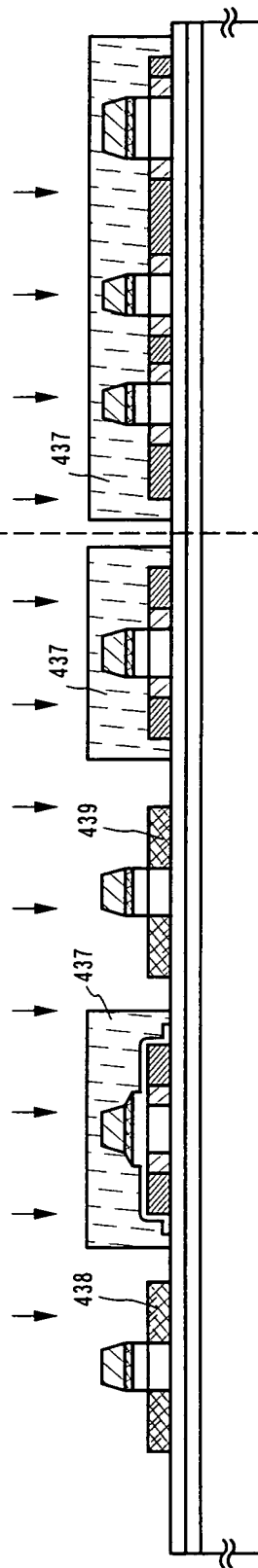


FIG. 6B

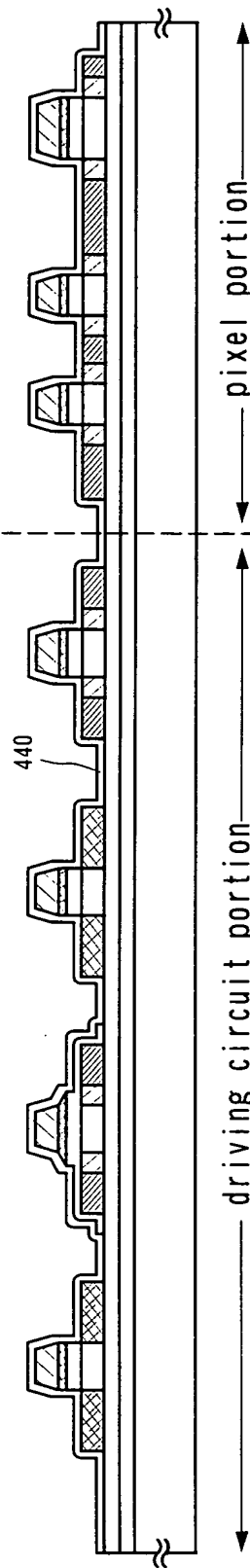


FIG. 6C

pixel portion

driving circuit portion

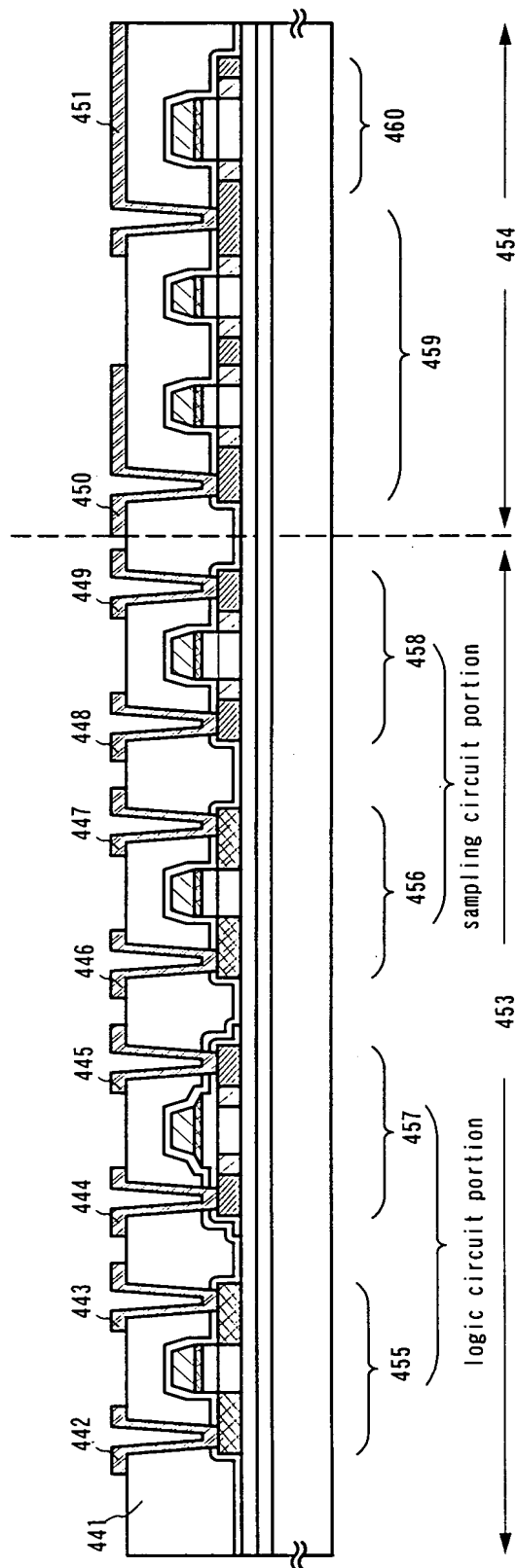


FIG. 7

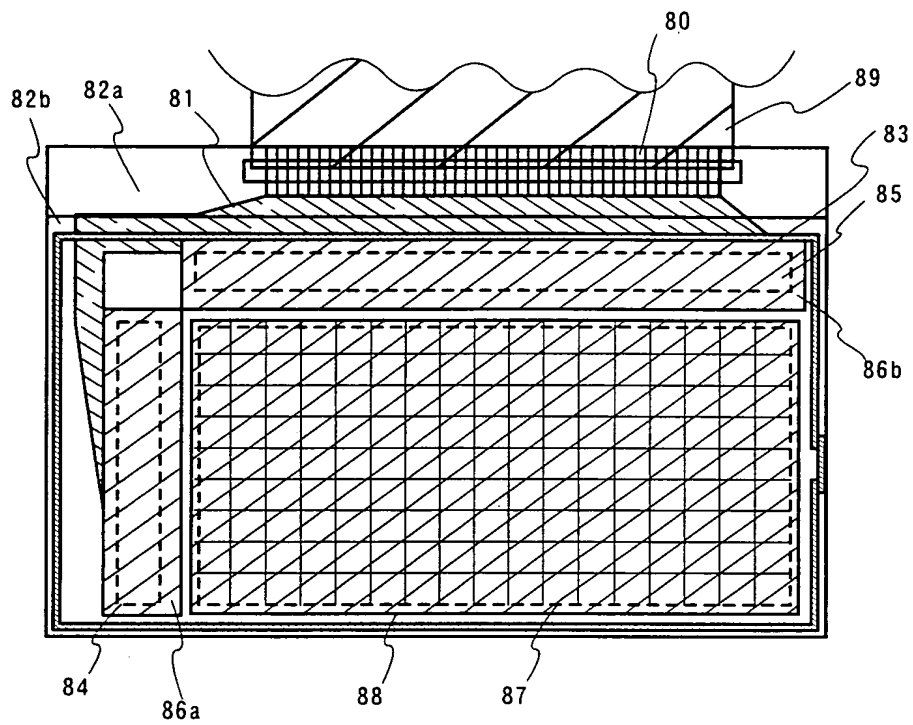


FIG. 8



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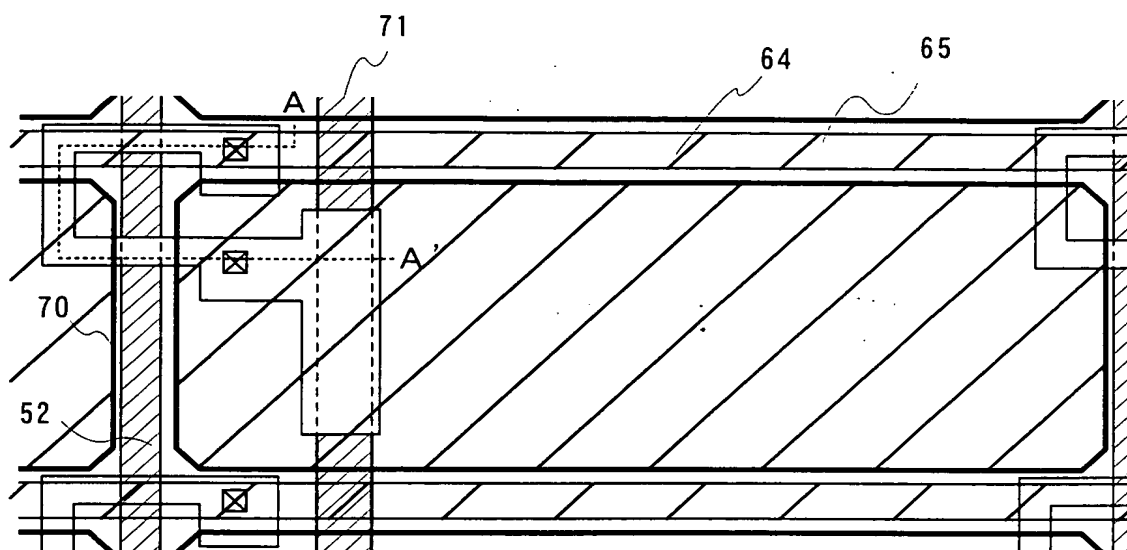


FIG. 9A

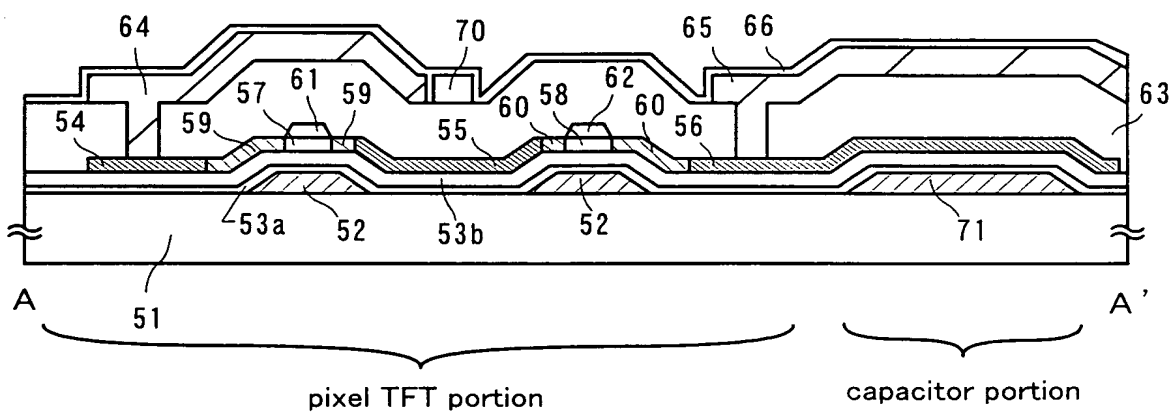


FIG. 9B

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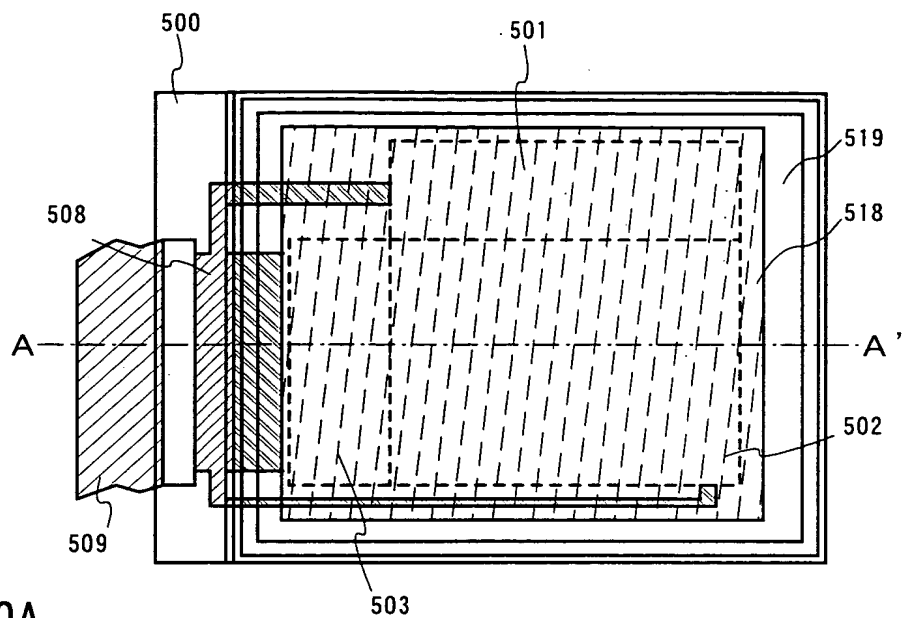


FIG. 10A

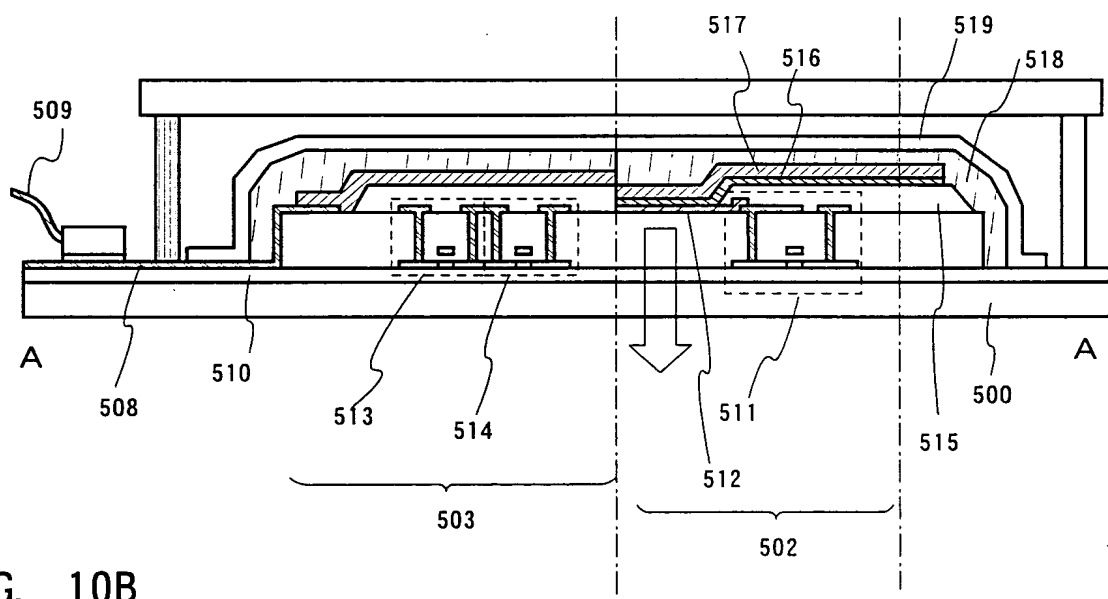


FIG. 10B

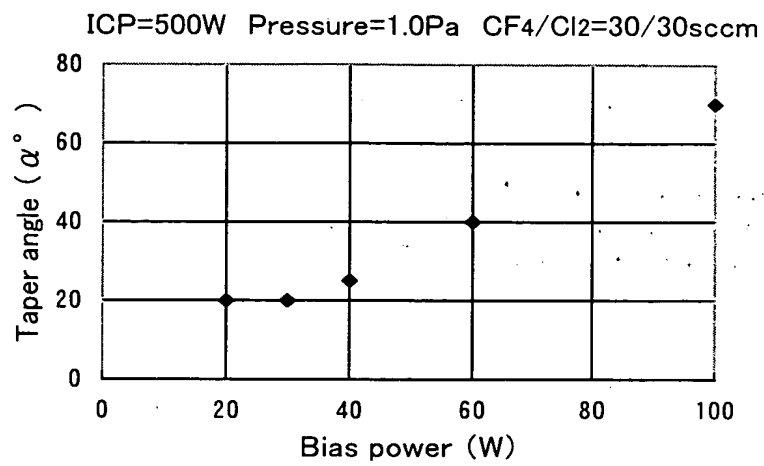


FIG. 11 Dependence of taper angle on bias power.

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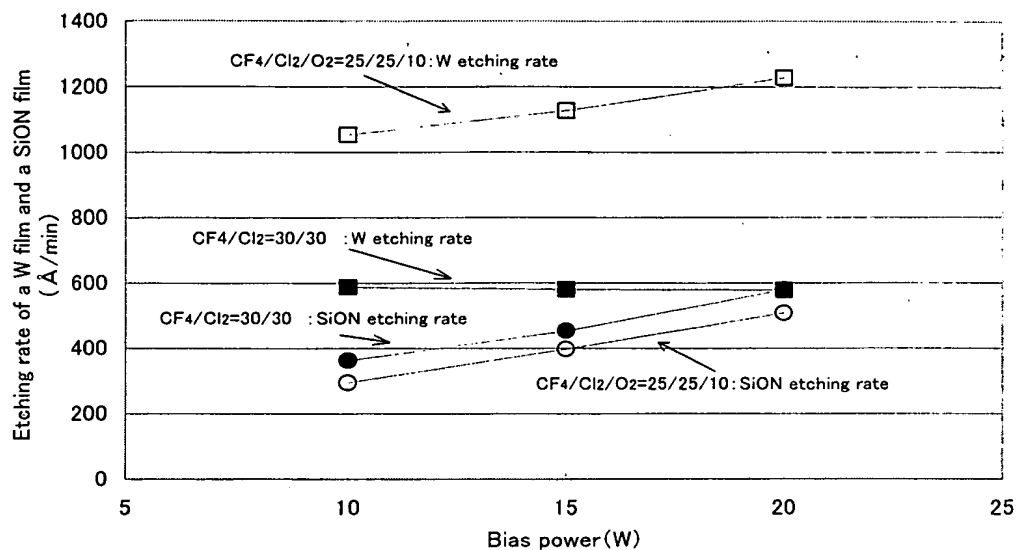


FIG. 12  
Dependence of an etching rate of a W film and an SiON film on bias power.

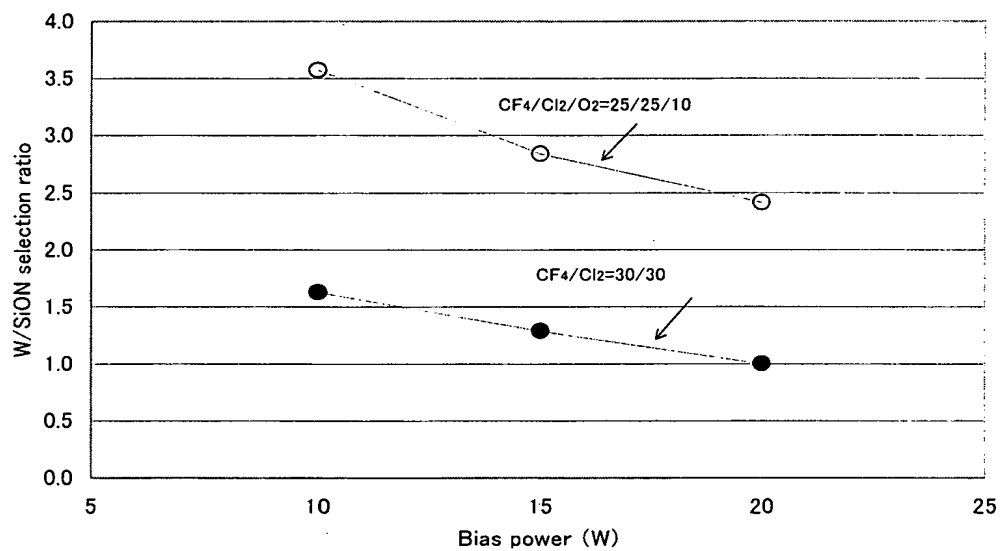


FIG. 13  
Dependence of a selection ratio between a W film and an SiON film on a bias power.

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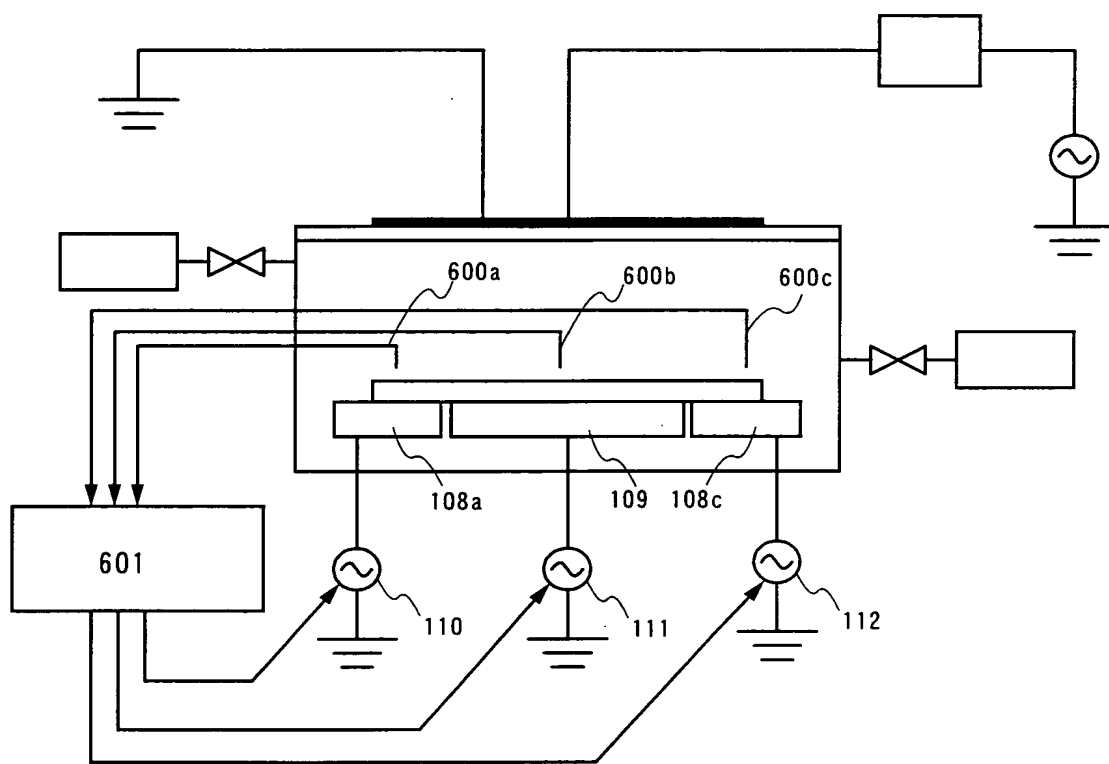


FIG. 14

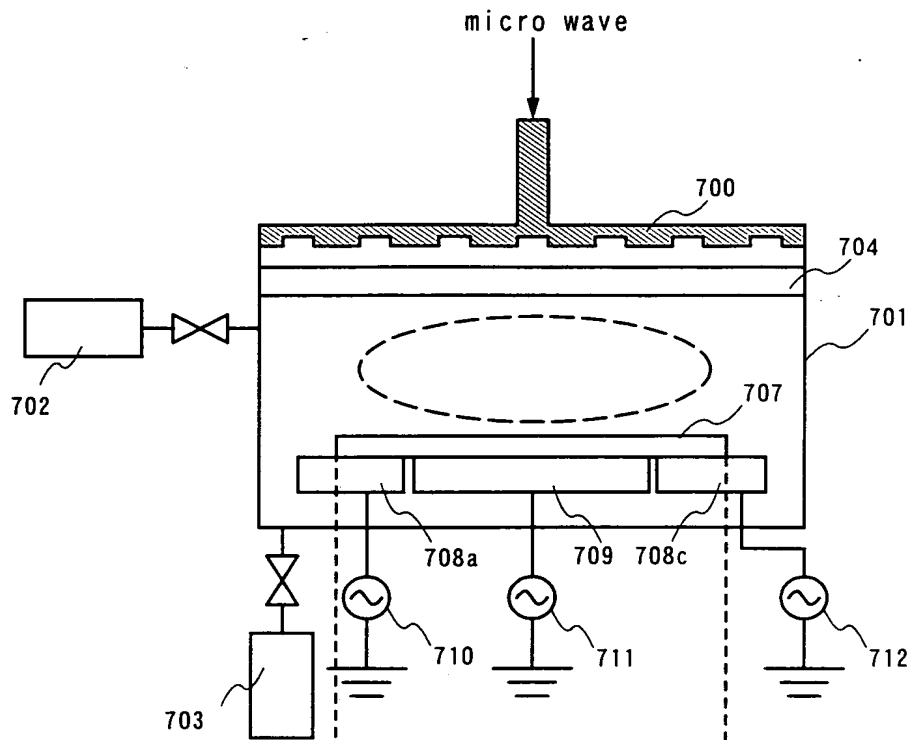


FIG. 15A

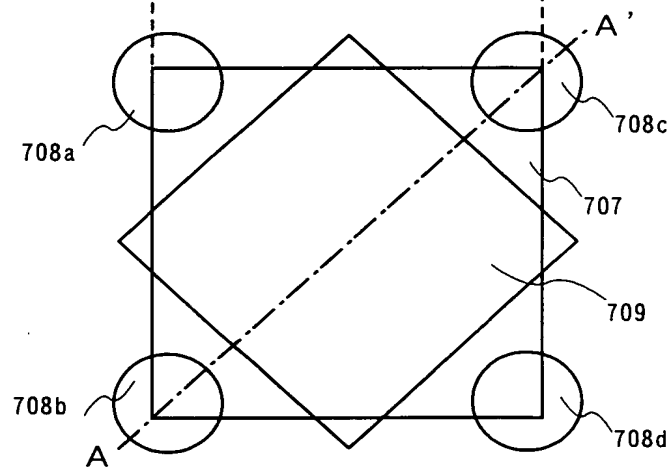


FIG. 15B

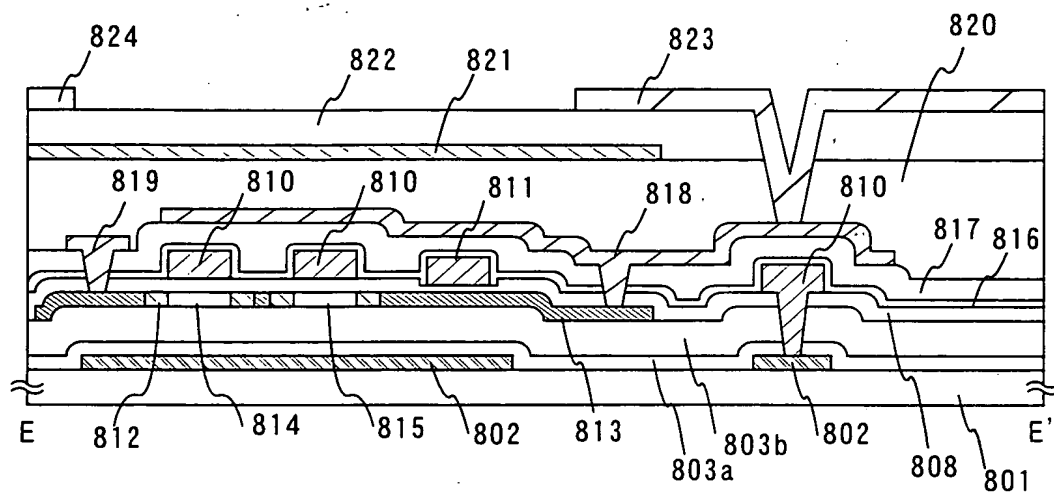


FIG. 16A

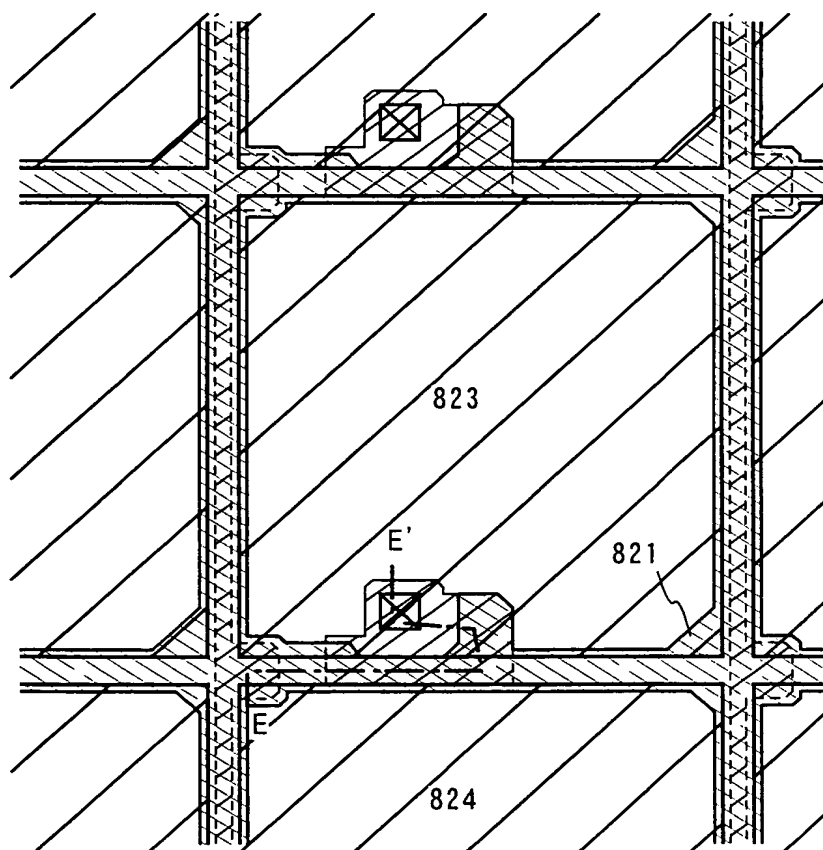


FIG. 16B

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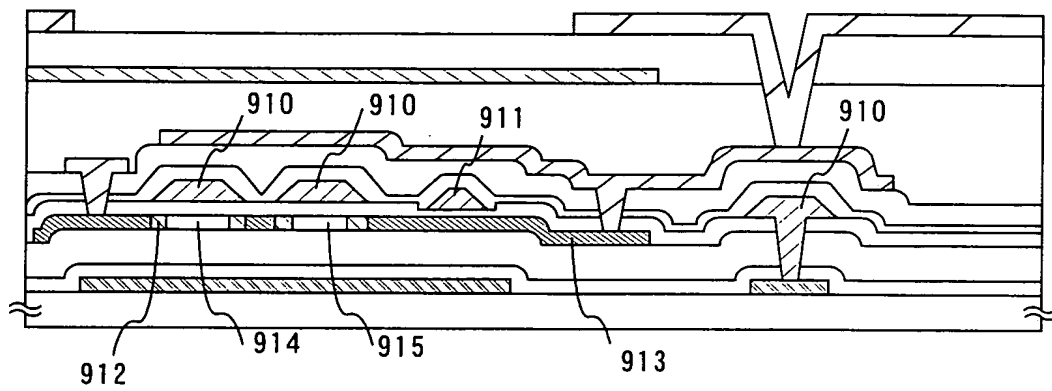


FIG. 17



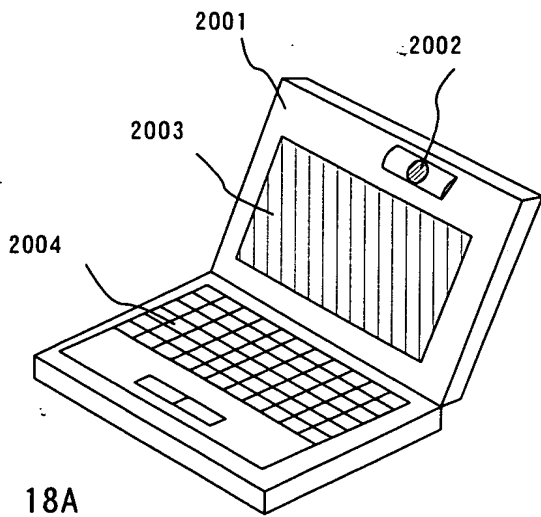


FIG. 18A

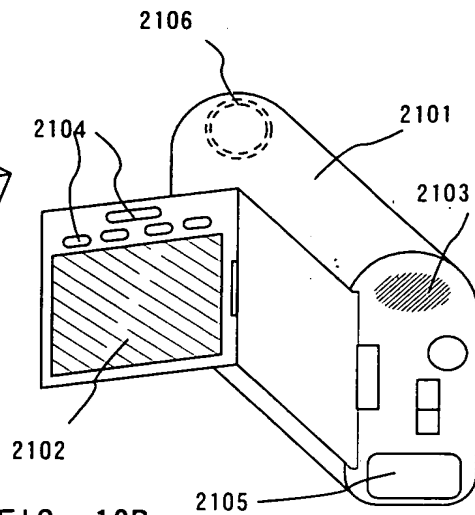


FIG. 18B

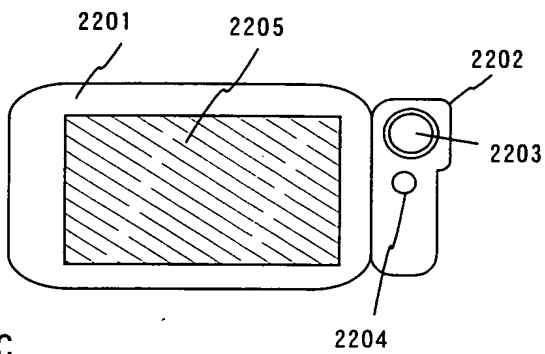


FIG. 18C

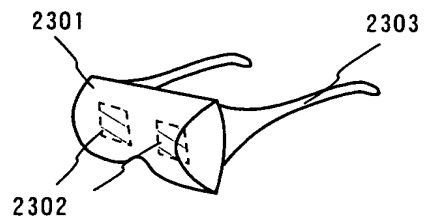


FIG. 18D

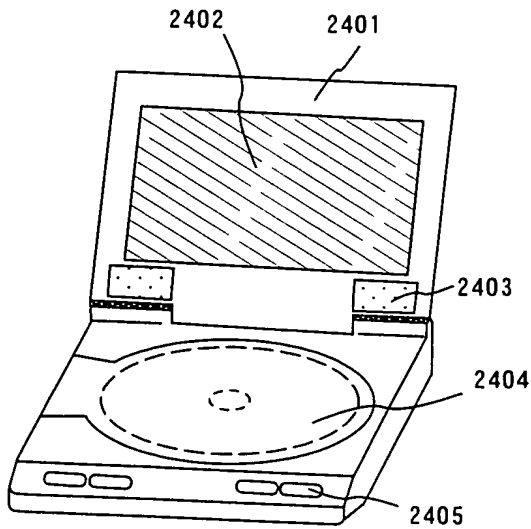


FIG. 18E

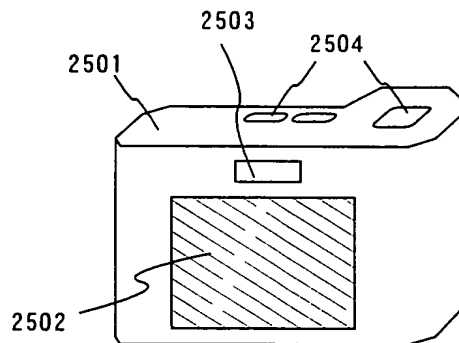


FIG. 18F

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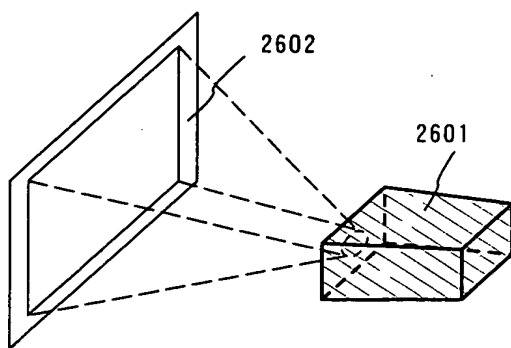


FIG. 19A

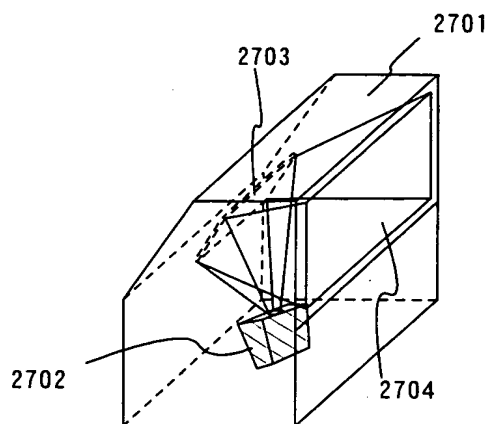


FIG. 19B

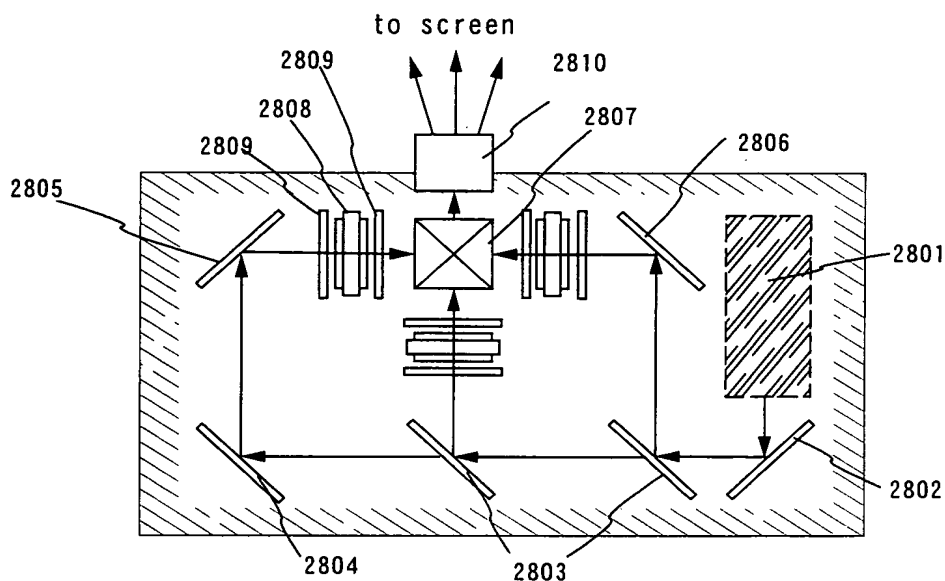


FIG. 19C

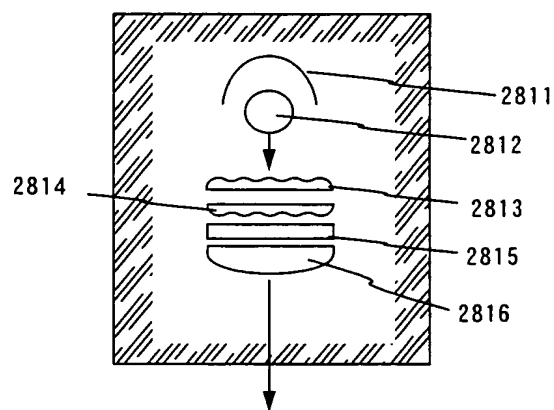


FIG. 19D

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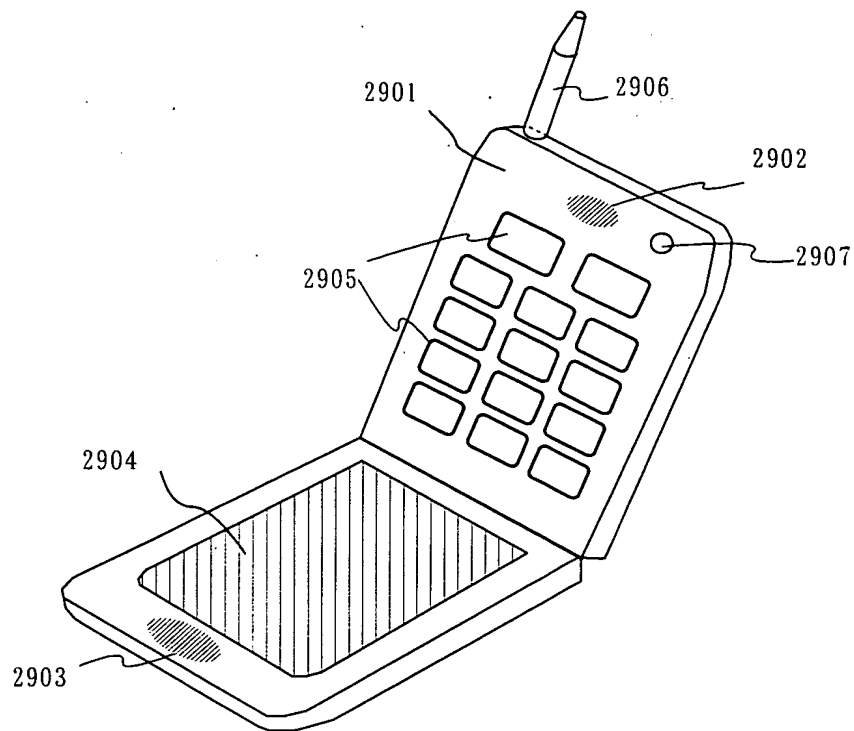


FIG. 20A

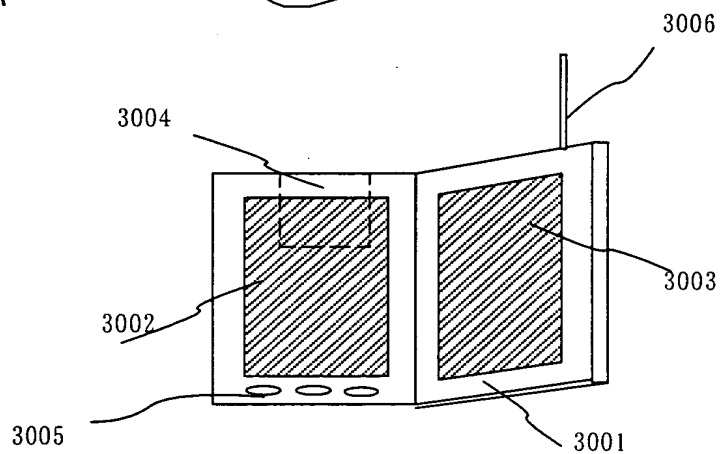


FIG. 20B

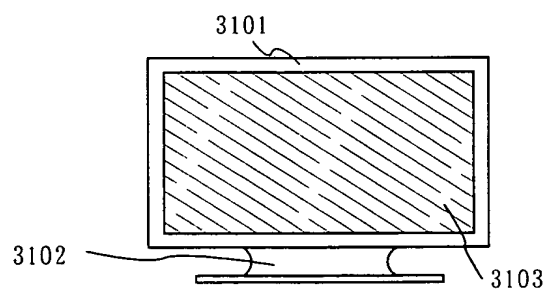


FIG. 20C

0996689-092701

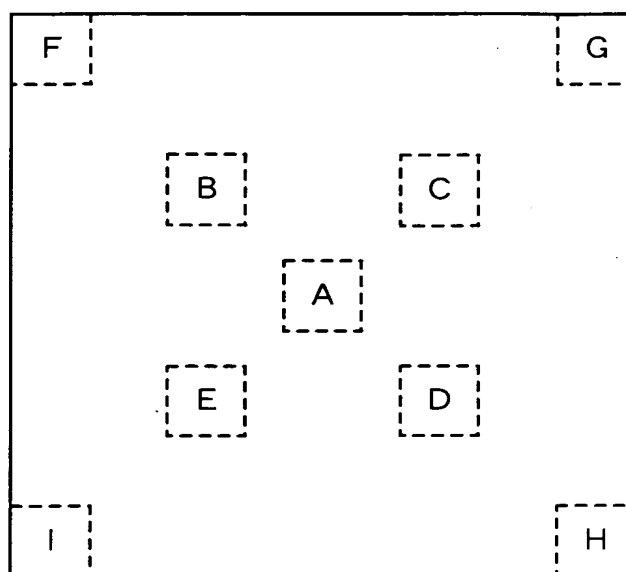


FIG. 21A

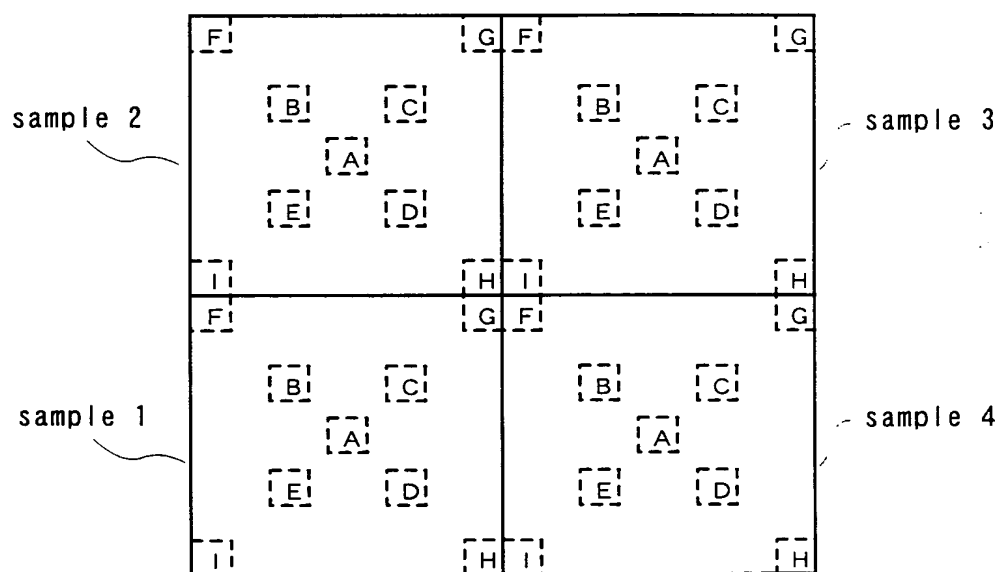


FIG. 21B